What is claimed is:

1. A reticle fabrication method comprising the steps of:

converting CAD (Computer Aided Design) data which is

5   reticle design data to electron beam write data by means of

a first data conversion device and to inspection data by

means of a second data conversion device;

comparing said electron beam write data with said

inspection data in a data verification device to verify

10   whether or not there is a data conversion error;

fabricating a reticle using said electron beam write

data after verifying that said electron beam write data is

data correctly converted from said CAD data; and

inspecting a quality of said reticle based on said

15   inspection data.

2. A reticle fabrication method comprising the steps of:

converting first electron beam write data for writing a

figure pattern on a reticle based on reticle design data to

20   second electron beam write data by means of a first data

conversion device and to inspection data by means of a

second data conversion device;

comparing said second electron beam write data with

said inspection data in a data verification device to verify

25   whether or not there is a data conversion error;

fabricating a reticle using said second electron beam write data after verifying that said second electron beam write data is data correctly converted from said first electron beam write data; and

5   inspecting a quality of said reticle based on said inspection data.

3. A reticle fabrication method comprising the steps of:

converting CAD (Computer Aided Design) data which is

10   reticle design data to electron beam write data by means of a first data conversion device;

comparing said electron beam write data with said CAD data in a data verification device to verify whether or not there is a data conversion error;

15   fabricating a reticle using said electron beam write data after verifying that said electron beam write data is data correctly converted from said CAD data; and

inspecting a quality of said reticle based on inspection data acquired by performing data conversion of

20   said electron beam write data by means of a second data conversion device.

4. A reticle fabrication method comprising the steps of:

converting CAD (Computer Aided Design) data which is

25   reticle design data to first electron beam write data and

second electron beam write data by means of a first data

conversion device and to first inspection data and second

inspection data by means of a second data conversion device;

comparing said first electron beam write data with said

5   first inspection data in a first data verification device to

verify whether or not there is a data conversion error;

comparing said second electron beam write data with

said second inspection data in a second data verification

device to verify whether or not there is a data conversion

10   error;

fabricating a reticle using said first and second

electron beam write data after verifying that said first and

second electron beam write data are data correctly converted

from said CAD data; and

15   inspecting a quality of said reticle based on said

first and second inspection data.

5.   The reticle fabrication method according to claim

1, wherein said data verification device verifies whether or

not there is a data conversion error by converting said

20   electron beam write data and said inspection data to raster

images to be used by an electron beam writing device of a

raster scan and stage continuous moving type and comparing

said raster images with each other.

6.   The reticle fabrication method according to claim

25   2, wherein said data verification device verifies whether or

not there is a data conversion error by converting said

electron beam write data and said inspection data to raster

images to be used by an electron beam writing device of a

raster scan and stage continuous moving type and comparing

5   said raster images with each other.

       7. The reticle fabrication method according to claim

3, wherein said data verification device verifies whether or

not there is a data conversion error by converting said

electron beam write data and said inspection data to raster

10   images to be used by an electron beam writing device of a

raster scan and stage continuous moving type and comparing

said raster images with each other.

       8. The reticle fabrication method according to claim

4, wherein said data verification device verifies whether or

15   not there is a data conversion error by converting said

electron beam write data and said inspection data to raster

images to be used by an electron beam writing device of a

raster scan and stage continuous moving type and comparing

said raster images with each other.

20   9. The reticle fabrication method according to claim

1, wherein said data verification device verifies whether or

not there is a data conversion error by converting said

electron beam write data and said inspection data to two-

dimensional coordinate data and comparing said two-

25   dimensional coordinate data with each other.

10. The reticle fabrication method according to claim 2, wherein said data verification device verifies whether or not there is a data conversion error by converting said electron beam write data and said inspection data to two-dimensional coordinate data and comparing said two-dimensional coordinate data with each other.

11. The reticle fabrication method according to claim 3, wherein said data verification device verifies whether or not there is a data conversion error by converting said electron beam write data and said inspection data to two-dimensional coordinate data and comparing said two-dimensional coordinate data with each other.

12. The reticle fabrication method according to claim 4, wherein said data verification device verifies whether or not there is a data conversion error by converting said electron beam write data and said inspection data to two-dimensional coordinate data and comparing said two-dimensional coordinate data with each other.